# • 2D Ballistic FET (83-114)

• General Expression for currents

# • 2D effects

• Bias self-consistency

# **2D Ballistic FET**



Carriers are confined to the xy-plane

Electron velocities – distributed as  $v_x$  and  $v_y$  $v_x$  gives conduction current

Subbands  $E_1(x)$ ,  $E_2(x)$ 

The device width W is assumed to be large – neglect quantization in y direction

## **Numerical 2D Ballistic Modeling**

J.-H. Rhew et al. / Solid-State Electronics 46 (2002) 1899-1906



## **Numerical 2D Ballistic Modeling**



#### **Current Saturation**



## **2D Ballistic MOSFET Currents / Charges**



$$n_{s}^{+}(0) = \frac{1}{A} \sum_{k_{x},k_{y}>0} f_{0}(E_{F})$$

$$J^{+} = \frac{1}{A} \sum_{k_{x},k_{y}>0} qv_{x}f_{0}(E_{F})$$

$$n_{s}^{-}(0) = \frac{1}{A} \sum_{k_{x},k_{y}<0} f_{0}(E_{F} - qV_{D})$$

$$J^{-} = \frac{1}{A} \sum_{k_{x},k_{y}<0} qv_{x}f_{0}(E_{F} - qV_{D})$$

$$\int g(\mathbf{k}) \rightarrow \frac{A}{(2\pi)^{2}} \int_{\mathbf{k}} g(\mathbf{k})d\mathbf{k}$$

## **2D Ballistic MOSFET Currents / Charges**



$$n_{s}^{+}(0) = \frac{N_{2D}}{2} F_{0}(\eta_{F})$$

$$n_{s}^{-}(0) = \frac{N_{2D}}{2} F_{0}(\eta_{F} - qV_{D})$$

$$J^{+} = \frac{qN_{2D}}{2} v_{T} [F_{1/2}(\eta_{F1})]$$

$$J^{-} = \frac{qN_{2D}}{2} v_{T} [F_{1/2}(\eta_{F1} - U_{D})]$$

$$J^+ = q n_s^+ v^+$$

$$v^{+} = v_{T} \frac{F_{1/2}(\eta_{F})}{F_{0}(\eta_{F})}; v_{T} = \sqrt{\frac{2kT}{\pi m^{*}}}$$

$$v^{-} = v_{T} \frac{F_{1/2}(\eta_{F} - U_{D})}{F_{0}(\eta_{F} - U_{D})}$$

#### I<sup>+</sup>: T=300K



## **Quantum Capacitance / Bias self consistency**

$$V'_{G} = \psi_{S} + Q/C_{ox}$$

$$V'_{G} = -\frac{\varepsilon_{1}(0)}{q} + \frac{qn_{s}(\varepsilon_{1})}{C_{ox}}$$

$$n_{s} = \frac{N_{2D}}{2} \{F_{0}(\eta_{F}) + F_{0}(\eta_{F} - U_{D})\}$$
Solve for  $\eta_{F}$ 
Semiconductor
$$\int_{\nabla} F_{s} = \frac{qN_{2D}}{2} v_{T}[F_{1/2}(\eta_{F})]$$

$$\int_{\Gamma} = \frac{qN_{2D}}{2} v_{T}[F_{1/2}(\eta_{F} - U_{D})]$$
MOS-limit:  $C_{ox} << C_{S}: n_{s} \text{ constant}$ 
Bipolar limit:  $C_{$ 

## Modeled 2D I-V



### **Degenerate expressions with Quantum Capacitance**

$$I^{+} \approx \frac{qW2\sqrt{2m^{*}}}{3\pi^{2}\hbar^{2}} \left(\frac{qC_{ox}}{C_{ox}+C_{s}}\right)^{\frac{3}{2}} (V_{GS}-V_{T})^{\frac{3}{2}} \qquad C_{s} = \frac{C_{q}}{2} = \frac{m^{*}}{2\pi\hbar^{2}}$$

$$V_{ds,sat} \approx \frac{V_{GS} - V_T}{1 + \frac{C_q}{2C_{ox}}}$$

$$G_{CH} = \frac{q^2 W \sqrt{2m^*}}{\pi^2 \hbar^2} \sqrt{q \frac{C_{ox}}{C_{ox} + C_q} (V_G - V_T)}$$

Minimum on-resistance: 
$$R_{on} = \frac{1}{G_{CH}}$$

A ballistic FET/conductor has a minimum on-resistance!

This is important when trying to extract  $R_c$  from measured data.





## **MOS statistics – MOS Limit**



 $C_{ox} \ll C_S, C_q$  $n_s = n_s^+(E_F) + n_s^-(E_F, V_D) = C_{ox}(V_{GS} - V_T)/q$ 

Charge at the top of the barrier is constant, independent of  $V_{\rm D}$ 

This is correct if  $C_{ox} \ll C_s$  and above  $V_T$ 

 $E_{\rm F}$ - $\varepsilon_1$  needs to increase as  $V_{\rm D}$  increases

Allows us easily to solve for  $\eta_{\rm F}$  And to relate  $n_{\rm s}$  to  $V_{\rm GS}$ 

- 1) No 2D effects
- 2) Large DOS, thick  $C_{ox}$

#### **2D Electrostatics – ballistic FETs**

$$V'_{G} = -\frac{\varepsilon_{1}(0)}{q} + \frac{qn_{s}(\varepsilon_{1}(0))}{C_{ox}} \quad \text{1D}$$

$$\varepsilon_{1}(0) = U_{L} + U_{P}$$

$$U_{L} = \alpha_{G}V_{G} + \alpha_{D}V_{D} + \alpha_{S}V_{S} \quad \text{Laplace Eq.}$$

$$U_{P} = \frac{q^{2}}{C_{\Sigma}}n_{s}(\varepsilon_{1}(0)) = U_{C}n_{s} \quad \text{Mobile Charge/Possion Eq.}$$

 $\alpha_{\rm G}$  : subthreshold slope,  $g_{\rm m}$  $\alpha_{\rm D}$ : DIBL/ $g_{\rm d}$  $E_{\rm F}$ : correct off-current  $V_{\sf g}$ 

 $V_{\rm S} \xrightarrow{\downarrow} C_{\rm G}$   $V_{\rm S} \xrightarrow{\downarrow} || \xrightarrow{\downarrow} V_{\rm D}$   $V_{\rm S} \xrightarrow{\downarrow} V_{\rm D}$ 

# **Quantum / Semiclassical**



**Quantum:** T(E)<1 above E(0) due to reflections T(E)>0 below E(0) due to tunneling

Quantum effects are **small** for  $L_a=10$  nm (Si) devices!